

ADVANCED CLEAN LUBRICATION OF MEMS

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Abstract: CN_x-coatings exhibit friction coefficients below 0.01 when tested in a N₂ gas atmosphere during sliding against itself, Si₃N₄ or steel although these material combinations give friction coefficients higher than 0.1 in air. Wear rates are below 10⁻⁷ mm³/Nm. H-DLC coatings ask behave in a similar manner in N₂ gas atmosphere. Observed behaviors of these carbon based coatings in N₂ promise high potential of clean lubrication methods of MEMS.

Key words: CN_x, H-DLC, N₂, low friction, low wear

1. INTRODUCTION

The contact load of elements of MEMS generally ranges in nN~μN. When such contacts are lubricated with liquid, stiction of contact surfaces is caused by the meniscus force which generates problems in operating MEMS. Dispersion and/or evaporation of the liquid lubricants generate another problem of contamination of the system.

Traditional solid lubricants such as graphite and MoS₂ are not suitable for MEMS as they are not supplied continuously and their solid particles in nm~μm are too large and too contaminant for the system to be accepted.

By considering those difficulties in applying traditional lubricants of liquids and solids to MEMS, N₂ gas lubrication[1] of carbon based coatings is introduced in this paper as the advanced clean method of lubrication of MEMS.

2. CARBON NITRIDE COATINGS (CN_x)

Hard coatings are supposed to be used for the elements of MEMS. CN_x-coatings introduced in this paper are produced on disks of Si-wafers or Si₃N₄ by having the deposition of carbon from a solid carbon target of 99.999% purity together with the mixing of nitrogen ions irradiated simultaneously from the ion beam gun. The carbon for the coating on Si-disk is sputtered from a carbon target by argon ion, and on Si₃N₄ disk it is evaporated by heating with electron beam.

The thickness of coatings ranges in 100~400nm and the surface average roughness Ra ranges 0.1~0.3nm on Si-disk and 20~80nm on Si₃N₄ disk. The hardness of coatings is about 30GPa in indentation depth from 10 to 50nm. The atomic concentration of

nitrogen in the CN_x-coatings is observed as 12~13% and the microstructure of coatings in amorphous.

3. FRICTION OF Si₃N₄ PIN/CN_x-SI DISK IN VARIOUS GASES

Fig.1 shows the effect of surrounding gas or vacuum on friction coefficient of Si₃N₄ pin/CN_x-Si disk in air, O₂, CO₂ and N₂ of 7.4 × 10⁴ Pa, and vacuum of 2 × 10⁻⁴ Pa. CN_x-coatings are exposed to air for 1hr after deposition before the test in each gas or vacuum.

Among the gases, N₂ generates the lowest friction coefficient below 0.01[2].

Similar friction tests are carried in the gases of He and Ar with 1.0×10⁵ Pa and high friction coefficient values above 0.2 are observed. It means that the inertness of nitrogen does not give explanation for the low friction.

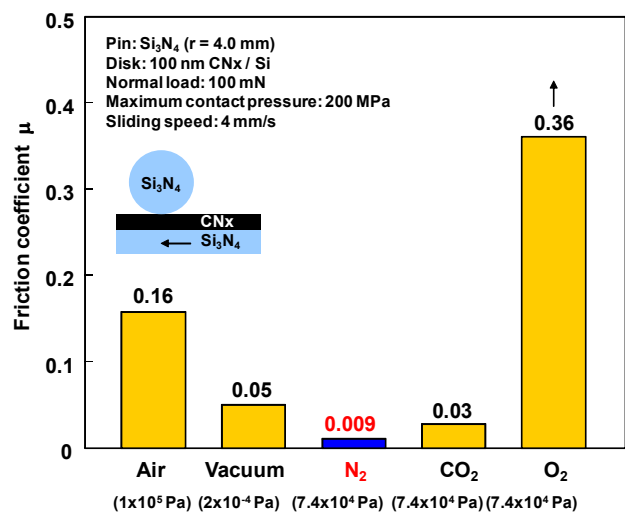


Fig. 1: The effect of gas on friction coefficient after 240 friction cycles at Si₃N₄pin/CN_x-Si disk[2].

4. FRICTION OF Si₃N₄ PIN/CN_x-SI DISK AND CN_x PIN/CN_x-DISK WITH N₂ GAS STREAM IN AIR ATMOSPHERE

When N₂ gas is supplied through a tube of 4.5mm diameter to the sliding interface between Si₃N₄ pin and CN_x coating on Si₃N₄ disk in air, high friction coefficient of 0.7 in air is effectively reduced as shown in Fig.2.

The amount of reduction in friction depends on the amount of N₂ gas supply, and the friction coefficient around 0.05 is generated by the supply of 4.8 l/min[3].

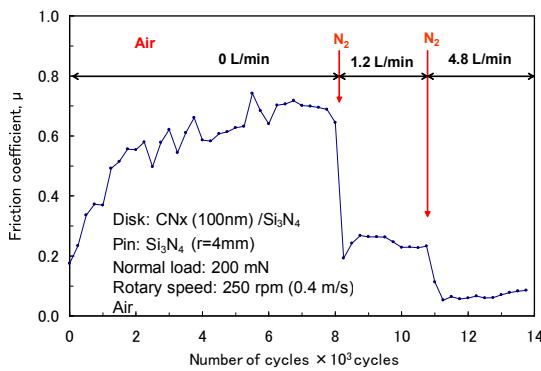


Fig.2: The effect of N₂ gas supply to the contact in air through a tube of 4.5mm diameter in sliding of Si₃N₄ pin against CN_x coating on Si₃N₄ disk [3].

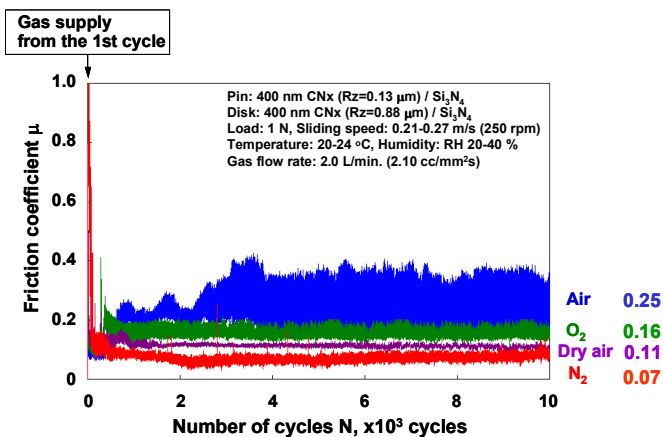


Fig.3: The effect of gas supply to the sliding interface between CN_x coatings on pin and disk of Si₃N₄.

5. THE SLIDING HISTORY EFFECT ON FRICTION OF CN_x-PIN/CN_x-DISK IN N₂ GAS STREAM

Fig.3 shows the change of friction between CN_x coatings on pin and disk of Si₃N₄ in the stream of gases of N₂, dry air and O₂ supplied through a tube of 4.5mm diameter in air. The friction coefficient μ in air is steady at around $\mu=0.25$, and it is reduced to about $\mu=0.07$ by having the stream of N₂ gas. The gas stream of O₂ and dry air give the friction coefficients of 0.16 and 0.11 respectively[4].

Fig.4(a) shows the same data for N₂ gas in Fig.3 on the semi-log scale. N₂ gas is supplied after the initial running-in of 100 friction cycles in air in Fig.4(b), and after 50 friction cycles in O₂ in Fig.4(c).

The steady state values of friction coefficient μ_s in Figs.3 and 4 are shown in Fig.5 together with the values of wear rate w_s [4].

The values of $\mu=0.05$ and $w_s=2.5 \times 10^{-8}$ mm³/Nm in the atmosphere of Air \rightarrow N₂ and those of $\mu=0.03$ and $w_s=5.0 \times 10^{-8}$ mm³/Nm in the atmosphere of O₂ \rightarrow N₂ are low enough for the practical usage in sliding elements of MEMS.

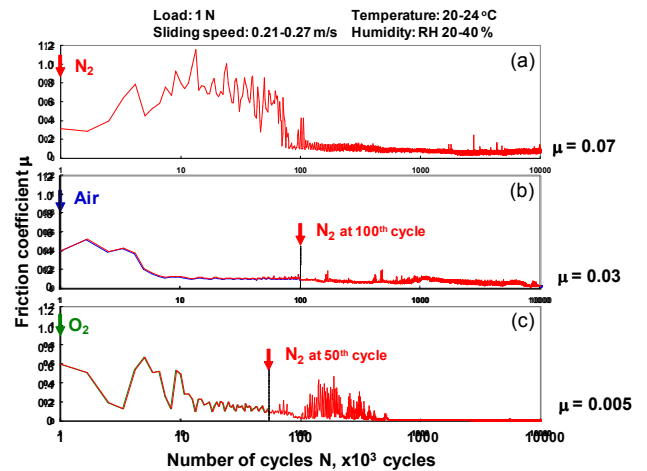


Fig.4: The effect of N₂ gas supplied to the contact after the running-in in air and in O₂ gas stream on reduction of friction coefficient between CN_x coatings on pin and disk of Si₃N₄ [4].

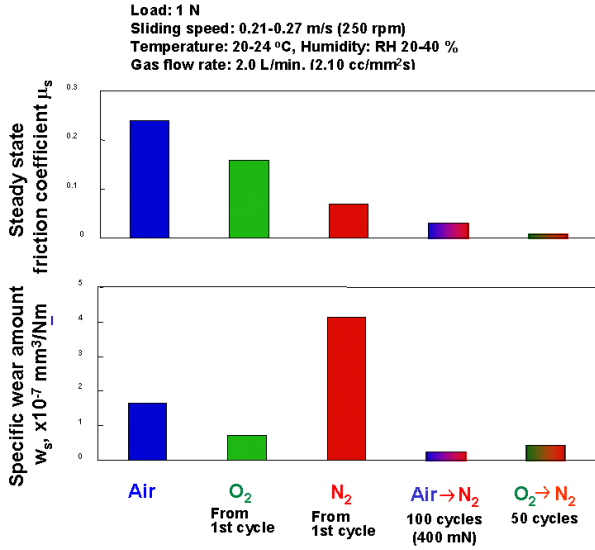


Fig.5: The values of friction coefficient μ of CN_x/CN_x and wear rate $w_s(\text{mm}^3/\text{Nm})$ of CN_x coating on Si_3N_4 pin in the stream of N_2 or O_2 and in air [4].

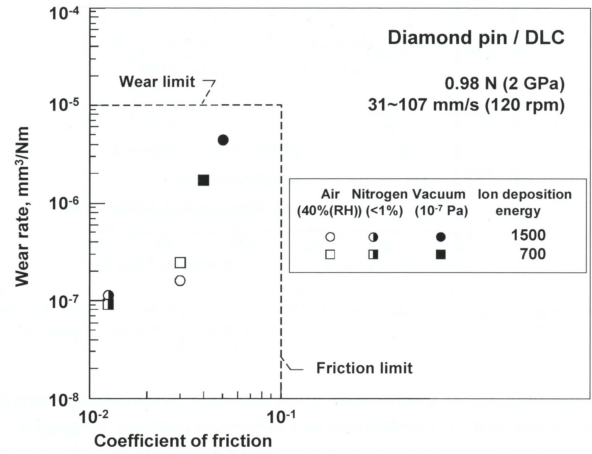


Fig.7: The effects of N_2 , air and vacuum on friction coefficient and wear rate in sliding of a diamond pin against DLC on disk[6]

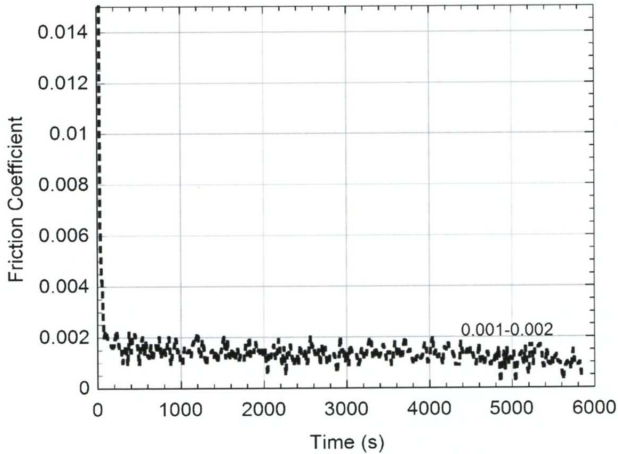


Fig.6: Low friction coefficient of a highly hydrogenated (~40 at % Hydrogen) DLC film coated on ball and disk of sapphire in dry nitrogen. Load: 10N, sliding velocity: 0.3m/s, temperature: 23 °C [5]

6. THE EFFECT OF N_2 ON FRICTION OF CARBON FILMS AND DIAMOND

Friction coefficients as low as 0.001 are observed with highly hydrogenated (~40 at % hydrogen) DLC films in N_2 gas as shown in Fig.6[5]. Surface layers of hydrogen are supposed to form on the friction surfaces. The friction coefficients below 0.01 are observed between diamond and DLC in N_2 gas as shown in Fig.7[6]. It is very clear from the observations in Figs.1~7 that N_2 gas works to reduce friction between carbon based films and diamond, although mechanisms of generating low friction is not yet understood[7].

7. CONCLUDING REMARKS

MEMS may require lubrication method which does not generate problems of stiction and/or running out of prepared lubricants by wear at contacts. N_2 gas lubrication of the carbon based coatings offers the possible technology for such requirement. The attainable values of friction coefficient ($\mu < 0.01$) and wear rate ($w_s < 10^{-7} \text{ mm}^3/\text{Nm}$) are quite sufficient for practical application is the development of getting N_2 gas around the contacts.

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